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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

1722

In re the Application of

Attn: OIPE

Masahiro SAKURADA et al.

Application No.: 10/538,878

Docket No.: 124231

Filed: June 14, 2005

For: METHOD OF PRODUCING P-DOPED SILICON SINGLE CRYSTAL AND P-DOPED N-TYPE SILICON SINGLE CRYSTAL WAFER

REQUEST FOR CORRECTION OF PALM RECORDS

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Attached is a photocopy of the original filing receipt on which errors have been corrected in red. These errors are being brought to the attention of the Patent and Trademark Office so that it may correct its records. The originally filed application data sheet is attached.

Respectfully submitted,

William P. Berridge
Registration No. 30,024

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WPB:JOC/mps

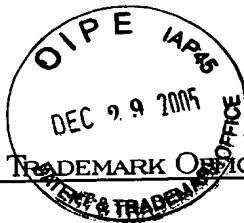
Date: December 29, 2005

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APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/538,878	06/14/2005	1722	1300	124231	4	28	2

CONFIRMATION NO. 8834

25944
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 ALEXANDRIA, VA 22320

DEC 15 2005

FILING RECEIPT



OC000000017601533

Date Mailed: 12/12/2005

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Applicant(s)

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Power of Attorney: The patent practitioners associated with Customer Number 25944.

Domestic Priority data as claimed by applicant

This application is a 371 of PCT/JP03/16794 12/25/2003

Foreign Applications

JAPAN 2003-10436 01/17/2003

Projected Publication Date: 03/16/2006

Non-Publication Request: No

Early Publication Request: No

Title

METHOD OF

Process for producing p-doped silicon single crystal and p-doped n-type silicon single crystal wafer



Preliminary Class

117

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